Monday, September 6

12:00-16:45 Short Course: Evolution and Progress of CMOS Logic Technology ～from the Past to the Future～
16:45-17:30 Panel Discussion

Tuesday, September 7

8:45-12:45 Opening & Plenary Sessions & Award Ceremony

Room A: Area1	Room B: Area 2	Room C: Area 3	Room D: Area 4	Room E: Area 5	Room F: Area 6	Room G: Area 7	Room H: Area 8	Room I: Area 9	Room J: Area 10	Room K: Area 11	Room L: Area 12
14:00-15:05 A-1:Quantum Computing and Cryo-CMOS			**14:00-15:19** D-1:GaN Devices and Related Technologies		**14:00-15:19** F-1:Energy Harvesting Devices	**14:00-15:19** G-1:Next-Generation Organic and Hybrid Materials for Device Applications		**14:00-15:12** I-1:Quantum Devices		**14:00-15:19** K-1:Nanomaterials and Nanofabrication I	**14:00-14:35** **Area2&12** **L-1:Advanced Memory Devices, Circuits and Systems**
Break											
	15:45-17:11 B−2:Non-Volatile-Memories and Emerging Devices		**15:45-16:50** D-2:Advanced Power Devices and Modules	**15:45-16:50** E-2:Tunable and Active Si Photonics	**15:45-16:36** F-2:Battery & Photocatalyst	**15:45-17:06** G-2:Organic Printed Electronics	**15:45-17:13** H-2:Growth and Synthesis: Low Dimensional Devices and Materials	**15:45-16:43** I-2:Neuromorphic and Novel Functional Devices	**15:45-17:11** J-2:Oxide TFTs and Sensors	**15:45-16:57** K-2:Nanomaterials and Nanofabrication II	**15:45-16:50** **Area1&12** **L-2:Innovative Device Based Circuits and Systems**

Wednesday, September 8

Room A: Area1	Room B: Area 2	Room C: Area 3	Room D: Area 4	Room E: Area 5	Room F: Area 6	Room G: Area 7	Room H: Area 8	Room I: Area 9	Room J: Area 10	Room K: Area 11	Room L: Area 12
	9:00-10:12 **Area1&2** B-3:Ferroelectric and Emerging Devices		**9:00-10:05** D-3:Advanced Wide-Bandgap Devices								**9:00-9:51** **L-3:Integrated Circuits for Next Generation Applications**
Break											
10:45-12:20 A-4:Advanced CMOS: Materials and Process		**10:45-11:57** C-4:3D Integration	**10:45-12:11** D-4:SiC Power Devices		**10:45-11:50** F-4:Compound Semiconductor Solar Cells		**10:45-11:57** H-4:Characterization I: Low Dimensional Devices and Materials		**10:45-12:04** J-4:Group IV Thin-Film Processing and Devices	**10:45-12:18** K-4:Advanced Crystal Growth and Characterization	**10:45-11:27** **Area7&12** L-4:Integrated Circuits for IoT and Sensing Applications
Lunch											
14:00-14:35 A-5:Ferroelectric: Materials and Devices	**14:00-15:19** B-5:Memory Computing and New Applications	**14:00-15:05** C-5:MEMS and Emerging Devices		**14:00-15:05** E-5:III-V Light Sources	**14:00-14:58** F-5:Silicon-based Solar Cells	**14:00-15:19** G-5:High-Sensitivity Biological and Chemical Sensing	**14:00-15:12** H-5:Characterization II: Low Dimensional Devices and Materials	**14:00-15:05** I-5:Spintronic Devices I	**14:00-15:19** J-5:Advanced Oxide Devices and Characterizations	**14:00-14:49** K-5:Thin Films, Surfaces and Processing Technology	**14:00-14:51** **Area4&12** L-5:Innovative Power Device and Circuit Technologies
Break											
15:45-17:18 A-6:RF, 3D stacking, Image Sensor, Modeling and Characterization	**15:45-16:57** B-6:Ferroelectric Memory Devices	**15:45-16:50** C-6:Advanced Metallization	**15:45-16:50** D-6:Ga2O3 & SiC Devices and Fundamentals	**15:45-16:50** E-6:New Materials for Photonics	**15:45-16:50** F-6:Perovskite & Chalcopyrite Solar Cells	**15:45-17:04** G-6:Microsystems for Biological Applications	**15:45-17:11** H-6:Device Application: Low Dimensional Devices and Materials	**15:45-16:50** I-6:Spintronic Devices II	**15:45-17:04** J-6:Emerging Solution Process Device Applications	**15:45-17:04** K-6:Group IV Materials	

Thursday, September 9

Room A: Area1	Room B: Area 2	Room C: Area 3	Room D: Area 4	Room E: Area 5	Room F: Area 6	Room G: Area 7	Room H: Area 8	Room I: Area 9	Room J: Area 10	Room K: Area 11	Room L: Area 12
9:00-10:12 A-7:Advanced CMOS: Device Technology			**9:00-10:19** D-7:GaN Power Devices and Process Technologies								
Break											
10:45-11:20 **Area1&10** A-8:IGZO for Integrated Devices											

Area Scope
- Area 1: Advanced CMOS: Material Science / Process Engineering / Device Technology
- Area 2: Advanced and Emerging Memories / New Applications
- Area 3: Interconnect / 3D Integrations / MEMS
- Area 4: Power / High-speed Devices and Materials
- Area 5: Photonics: Devices / Integration / Related Technology
- Area 6: Photovoltaics / Energy Harvesting / Battery-related Technology

Area Scope
- Area 7: Organic / Molecular / Bio-electronics
- Area 8: Low Dimensional Devices and Materials
- Area 9: Novel Functional / Quantum / Spintronic Devices and Materials
- Area 10: Thin Film Electronics: Oxide / Non-single Crystalline / Novel Process
- Area 11: Advanced Materials: Synthesis / Crystal Growth / Characterization
- Area 12: Advanced Circuits / Systems Interacting with Innovative Devices and Materials